

ISO 16413:2013-02 (E)

Evaluation of thickness, density and interface width of thin films by X-ray reflectometry - Instrumental requirements, alignment and positioning, data collection, data analysis and reporting

Contents	Page
Foreword	iv
Introduction	v
1 Scope	1
2 Terms, definitions, symbols and abbreviated terms	1
2.1 Terms and definitions	1
2.2 Symbols and abbreviated terms	4
3 Instrumental requirements, alignment and positioning guidelines	4
3.1 Instrumental requirements for the scanning method	4
3.2 Instrument alignment	9
3.3 Specimen alignment	9
4 Data collection and storage	11
4.1 Preliminary remarks	11
4.2 Data scan parameters	11
4.3 Dynamic range	11
4.4 Step size (peak definition)	12
4.5 Collection time (accumulated counts)	12
4.6 Segmented data collection	12
4.7 Reduction of noise	13
4.8 Detectors	13
4.9 Environment	13
4.10 Data storage	13
5 Data analysis	14
5.1 Preliminary data treatment	14
5.2 Specimen modelling	14
5.3 Simulation of XRR data	16
5.4 General examples	16
5.5 Data fitting	19
6 Information required when reporting XRR analysis	21
6.1 General	21
6.2 Experimental details	21
6.3 Analysis (simulation and fitting) procedures	22
6.4 Methods for reporting XRR curves	23
Annex A (informative) Example of report for an oxynitrided silicon wafer	26
Bibliography	30